

<b>Form PTO-1449 (modified)</b>  List of Patents and Publications For Applicant's Information Disclosure Statement  (Use several sheets if necessary)	<b>ATTY. DOCKET NO.</b> MICS:0015--2 (93-118.02)	<b>SERIAL NO.</b> Unassigned
	<b>APPLICANT</b> Ravi Iyer	
	<b>FILING DATE</b> Herewith	<b>GROUP</b> 1104

**U.S. PATENT DOCUMENTS**

EXAM. INIT.	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
TN	A1	4,323,589	04/06/82	Ray et al.	427	38	05/07/80
↑	A2	4,408,387	10/11/83	Kiriseko	29	576	09/28/82
	A3	4,527,325	07/09/85	Geipel Jr., et al.	29	571	12/23/83
	A4	4,576,829	03/18/86	Kaganowicz et al.	427	39	12/28/84
	A5	4,604,304	08/05/86	Faraone et al.	427	255	07/03/85
	A6	5,026,665	06/25/91	Zdebel	437	191	12/24/90
	A7	5,043,224	08/27/91	Jaccodine et al.	428	446	04/05/90
	A8	5,182,221	01/26/93	Sato	437	67	06/12/91
	A9	5,310,720	05/10/94	Shin et al.	437	231	02/24/93
	A10	5,330,935	07/19/94	Dobuzinsky et al.	437	239	07/21/92
	A11	5,384,288	01/24/95	Ying	437	228	02/01/94
	A12	5,387,539	02/07/95	Yang et al.	437	67	01/18/93
	A13	5,391,508	02/21/95	Matsuoka et al.	437	41	12/21/93
	A14	5,438,016	08/01/95	Figura et al.	437	67	03/02/94
	A15	5,466,637	11/14/95	Kim	437	187	09/08/93
	A16	5,472,904	12/05/95	Figura et al.	437	67	08/08/94
↓	A17	5,508,209	04/16/96	Zhang et al.	437	21	09/27/94
TN	A18	5,567,638	10/22/96	Lin et al.	437	46	06/14/95

**FOREIGN PATENT DOCUMENTS**

EXAM. INIT.	REF. DES.	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION
TN	B1	2-114641	04/26/90	Japan	H01L21	3205	
TN	B2	60-70740	04/22/85	Japan	H01L21	76	

**OTHER ART (Author, Title, Journal, Volume, Pertinent Pages, & Date)**

TN	C1	Badih El-Kareh, "Fundamentals of Semiconductor Processing Technology," Kluwer Academic Publishers-Boston, pgs. 128-129.
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EXAMINER <i>Th...</i>	DATE CONSIDERED <i>7/29/98</i>
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.